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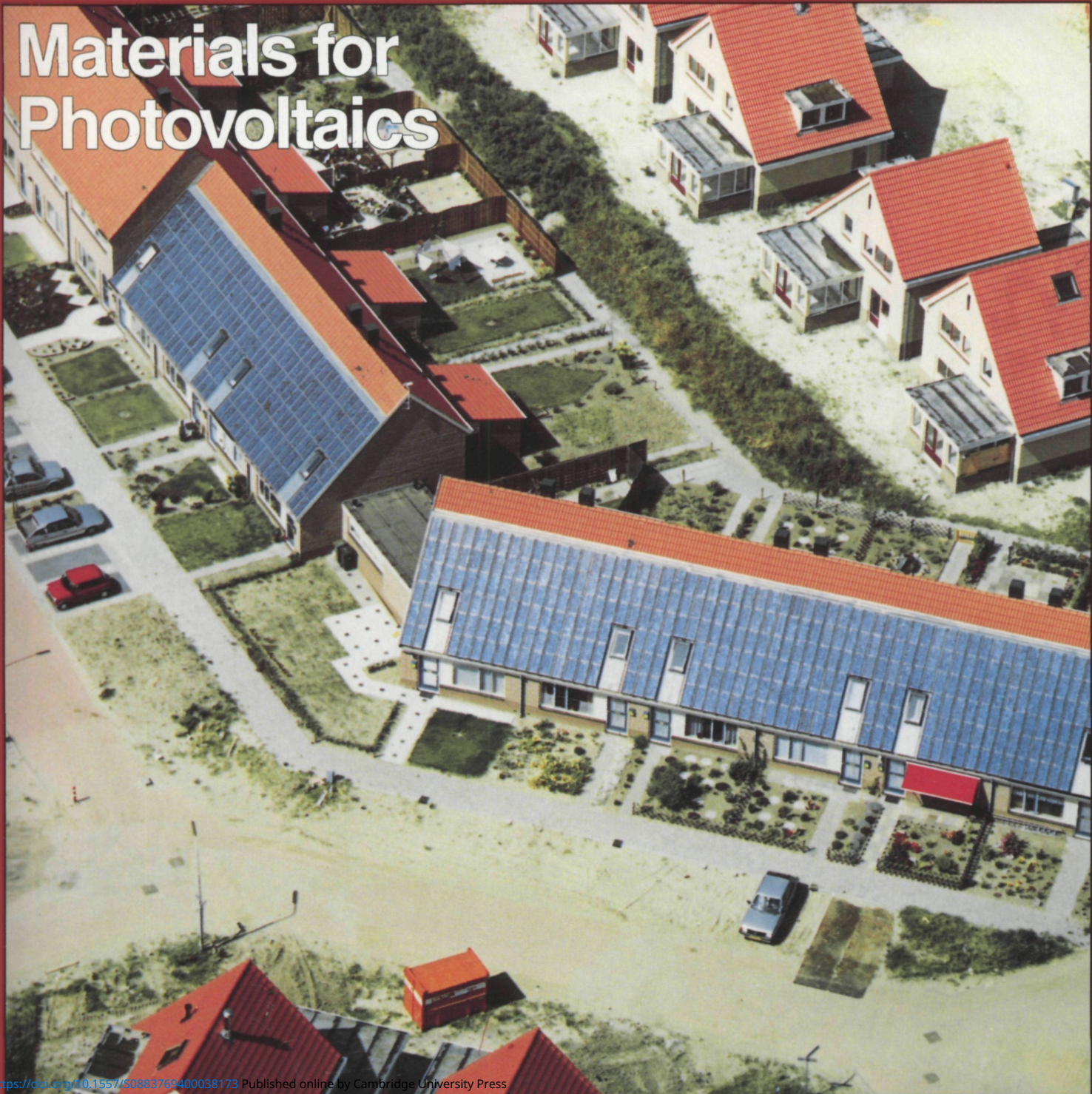
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Materials for Photovoltaics



HAVE YOU HEARD THE RUMOUR??

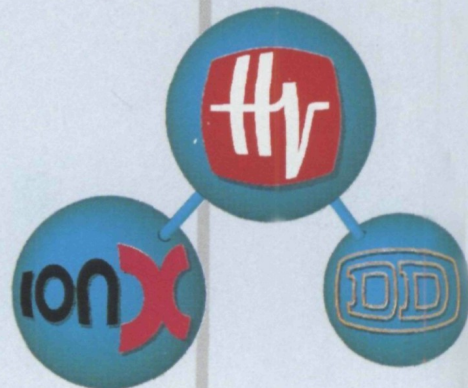
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ON THE COVER: Ten family houses equipped with roof-integrated photovoltaic systems. Location: Heerhugowaard, 50 km north of Amsterdam. Each system is approximately 1.5 kW-peak and connected to the 220 V grid. Systems are operated by the PEN Utility Company of the province of North-Holland. (Photo kindly provided by PEN.) For more information on materials for photovoltaics, see the section beginning on page 18.

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The Materials Research Society (MRS), a non-profit scientific association founded in 1973, promotes interdisciplinary goal-oriented basic research on materials of technological importance. Membership in the Society includes nearly 11,000 scientists, engineers, and research managers from industrial, government, and university research laboratories in the United States and nearly 50 countries.

The Society's interdisciplinary approach differs from that of single-discipline professional societies because it promotes information exchange across the many technical fields touching materials development. MRS sponsors two major international annual meetings encompassing approximately 50 topical symposia, and also sponsors numerous single-topic scientific meetings. The Society recognizes professional and technical excellence, conducts short courses, and fosters technical interaction in local geographic regions through Sections and University Chapters.

MRS participates in the international arena of materials research through the International Union of Materials Research Societies (IUMRS). MRS is an affiliate of the American Institute of Physics.

MRS publishes symposium proceedings, *MRS Bulletin*, *Journal of Materials Research*, and other publications related to current research activities.

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